IEEE Electron Device Letters EDL-8, 9, (1987)

Exposure Bleaching of Nonlinear Resist Materials: Exact Solution

S. V. Babu and E. Barouch

ABSTRACT

Dill's model equations for the exposure bleaching of positive photoresists have been solved exactly in a closed form when the bleaching characteristics are nonlinear. As an application, the simultaneous bleaching of a positive photoresist and that of a polysilane contrastenhancing film (CEF) is solved to determine the photoactive compound (PAC) concentration.